

METHOD OF PRODUCING A SHEET COMPRISING THROUGH PORES AND
THE APPLICATION THEREOF IN THE PRODUCTION OF MICRONIC AND
SUBMICRONIC FILTERS

5

A B S T R A C T

The method comprises the following steps:

- preparing a sheet having thickness of 5 μm to a
10 few tens of micrometers, suitable for being etched by a
lithographic operation;
- making a mask on a face of the sheet, the mask
presenting etching selectivity S of at least 5;
- depositing a layer of photosensitive resin on the
15 mask;
- making through holes in the layer of resin by
photolithography;
- etching through the mask via the pores in the
layer of resin; and
- 20 · anisotropically etching through the sheet from the
pores in the mask in order to make pores in the sheet
having an aspect ratio greater than 5.

The invention is applicable to fabricating micron
and sub-micron filters.

25

30

Translation of the title and the abstract as they were when originally filed by the
35 Applicant. No account has been taken of any changes that may have been made
subsequently by the PCT Authorities acting ex officio, e.g. under PCT Rules 37.2,
38.2, and/or 48.3.